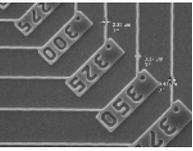
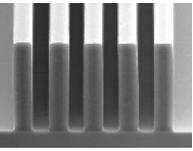
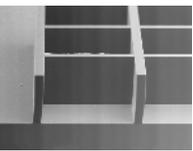


SU-8 Technology

Permanent Negative Epoxy Photoresists

Diverse Resist Options for Unique Needs

Product Line	Features	UV Sensitivity	Film Thickness (optimum)	Resolution
SU-8 TF 6000				
	<ul style="list-style-type: none"> High resolution thin film processing Highly uniform thin films Improved substrate adhesion 	g-, h-, i-line	0.5–10 μm	High Resolution
SU-8 3000				
	<ul style="list-style-type: none"> Improved substrate adhesion Reduced coating stress 	i-line	10–70 μm	>5:1 Aspect Ratio
SU-8 2000				
	<ul style="list-style-type: none"> Improved substrate wetting Faster drying Higher process throughput 	i-line	10–100 μm	>10:1 Aspect Ratio
SU-8				
	<ul style="list-style-type: none"> Wide range of viscosities High aspect ratio patterning Photo-definable ultra-thick structures 	i-line	10–200 μm	>10:1 Aspect Ratio

APPLICATIONS

- MEMS
- Microfluidics
- Optoelectronics
- Displays